

PART ONE: General description

Lithography3

Process name

UL3_003

Process Code

04/24/00

Last Update

Udo Lang

Author

lang@ee

Contact Information (Email)

AZ4620 two layers

General description of process

PART TWO: Details

Cleaning

Nano-strip
Time (min)

BOE
Time (min)

Rinse and Dry

Resist Coating

P-10
Primer Speed1 (RPM) Time(sec) Speed2 (RPM) Time(sec)

HMDS
 AZ 4620
Resist Speed1 (RPM) Time(sec) Speed2 (RPM) Time(sec)

PreBake
T (°C) Time(min)

AZ 4620
Speed1 (RPM) Time(sec) Speed2 (RPM) Time(sec)

PreBake
T (°C) Time(min)

Exposure
Time(sec)

Develop
Developer Time(sec)

PostBake
T (°C) Time(min)

Rinse and Dry

PART THREE: General Comments

4" aligner - 45 sec exposure